

Fig. 3 Before Capacitor Process

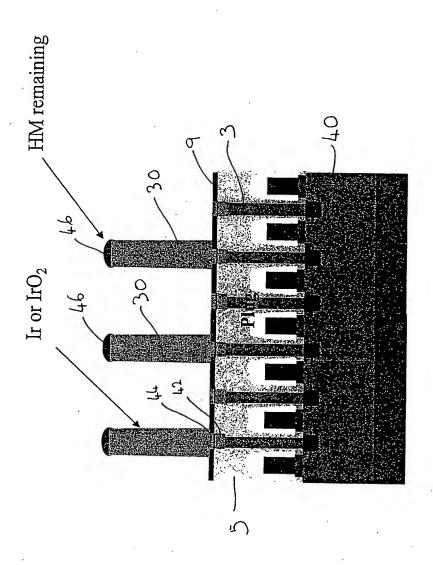


Fig. 4 Ir or IrO2 Deposit and RIE

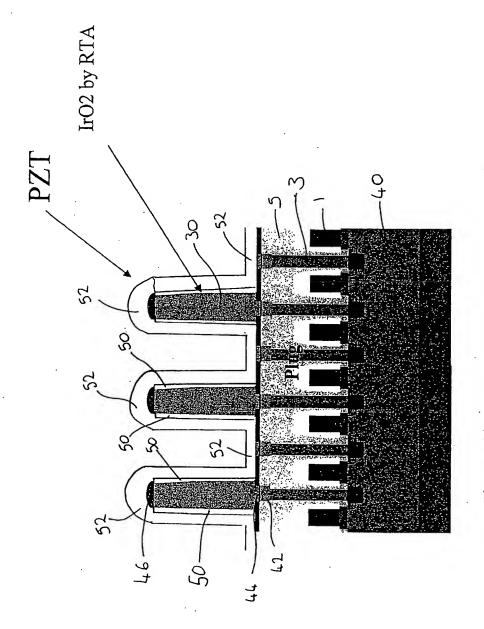


Fig 5 Making IrO2 on Ir surface (by RTA, if electrode is IrO2, RTA is not necessary) and PZT Deposit on Surface

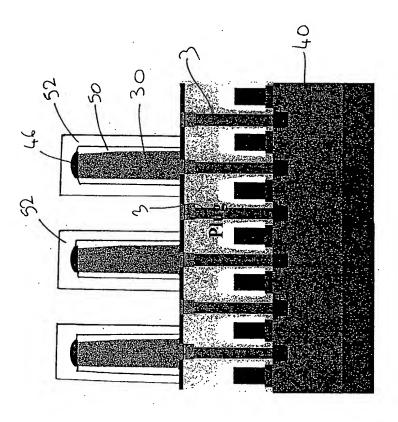


Fig. 6 PZT Etch Back

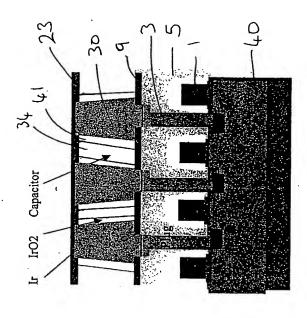


Fig. ⁷ Fill IrO2 and Fill Ir (Or Only fill IrO2) CMP and then Al2O3 deposit